

International Conference on Integrated Circuit Design & Technology

## **Call for Papers**

Paper Deadline: February 16<sup>th</sup>, 2012

International Conference on IC Design & Technology Austin, Texas; May 30<sup>th</sup> – June 1<sup>st</sup>, 2012



As IC design & process technology continue to advance toward increased performance, lower power, and accelerated time-to-market, engineering teams that are traditionally separated by the boundary between design and process technology will have difficulties meeting the shrinking window available for product optimization tasks. The International Conference on IC Design & Technology provides a forum for engineers, researchers, scientists, professors and students to cross this boundary through interactions directly focused on tying together design and process technology. The unique workshop style of the conference provides an opportunity to technologists and product designers to exchange breakthrough ideas and collaborate effectively. Two days of technical presentations and workshops will be preceded by a one-day tutorial program of value to both the expert and the beginner.

The venue for the 2012 ICICDT will be Freescale Semiconductor at 7700 W Parmer Lane, Austin, Texas, 78729, U.S.A.

(http://www.ICICDT.org)

## Papers are solicited on:

- Design approaches including system, circuit and EDA to manage power, leakage, process variation, signal integrity, reliability, yield, and manufacturability.
- Advanced VLSI design, including embedded and host processors, ASICs, memory sub-systems, analog and mixed-signal circuits.
- Multicore System-on-Chip (SoC), System-in-Package (SiP), and IP reuse for fast design closure.
- Advanced materials, advanced metallization, and 3D interconnection to realize novel interconnect schemes and future SoCs.
- Process and circuit technology for advanced memories: ReRAM, PRAM, MRAM, FeRAM, DRAM, Nanocrystal Memory, Flash, etc. with emphasis on reliability.
- Advanced transistor structures for bulk, multiple Gate (FinFET & Tri-gate FET), FDSOI, PDSOI, SSOI, SiGe, etc. technologies.
- RF & analog properties of advanced devices (MOS, BJT, MEMS ...) & analog circuits on advanced technologies (planar, heterogeneous, 3D...).
- New gate materials for adjusting Vt, enhanced mobility & scalability, low leakage, and low power.
- SER, thermal, leakage, Plasma-Induced Damage (PID), reliability, yield, etc. effects on advanced transistor structures and circuits.
- Simulation & modeling on advanced processes, devices & circuits.
- Nanotechnology materials, devices and circuits.
- ESD protection circuitry, mixed-voltage-tolerant I/O design, high speed and low power I/O buffers
- Emerging IC technology and circuit crossovers such as organic IC's, integrated sensors and integrated actuators.
- High Power, High Voltage devices and technology.







Prospective authors are invited to submit a camera-ready paper of maximum four pages in length, including figures and references. The authors should obtain paper submission guidelines from <u>http://www.ICICDT.org</u>. Accepted / Invited papers will be included in the proceedings of the conference (available on CD-ROM). Accepted papers must be accompanied by a non-refundable registration fee and presented at the conference to be published in IEEE Xplore.

## **Conference Format**

ICICDT features a popular and unique format structured to maximize face-to-face interaction. An abbreviated synopsis of each paper is presented in a plenary session, and following the presentations, a workshop-style forum allows for more detailed discussions on an individual basis. Many participants in previous years have commented that this interaction is very rewarding.

## **Contact Information**

For further general information or assistance in selecting a subject area, please contact:

General Chair Conference Chair Executive Committee Chair Local arrangement/AV chair Publication chair Publicity chair Tutorial chair Treasurer Secretary Chua-Chin Wang Geoffrey Yeap Thuy Dao Mark Hall Thomas Ea Terrence Hook Keith Bowman Thuy Dao Dina Triyoso ccwang@ee.nsysu.edu.tw gyeap@qualcomm.com thuy.dao@freescale.com mark.hall@freescale.com thomas.ea@isep.fr tbhook@us.ibm.com keith.a.bowman@intel.com thuy.dao@freescale.com dina.triyoso@globalfoundries.com

For technical assistance, please contact the appropriate sub-committee chair[s]:

Adv. Transistor / Materials

Advanced Memory Devices

CAD

DFM/DFT/DFR/DFY/SER High Power / High Voltage 3D Integration Low Power SoC/MPSoC/SIP

Reliability/PID

**Emerging Technologies** 

I/O Circuits and ESD Protection

RF & Analog, Mixed signal

Dong-Won Kim Bich-Yen Nauven Yoshinori Kumura Hideto Hidaka David Pan Gi-Joon Nam Rouwaida Kanj Jan Ackaert Bich-Yen Nguyen Michael Han Dac Pham Masaya Sumita Yuichiro Mitani Koii Eriauchi Simon Deleonibus Hiroshi Mizuta Ming-Dou Ker Dimitri Linten Andrea Scarpa

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